

patented *VACUUM-HOLDER*

Our patented Wafer Holder BASIC is a handling tool created for chemical etching of silicon wafers. The wafer disks are held securely by means of a vacuum, thus also protecting them reliably from the etching agent.

The protected area behind the wafer is ventilated to provide pressure compensation.

Penetrating fluids e.g. after a membrane fracture, can be removed by means of a cannula and a gear or hose pump (see accessories).

Equipment: Sealing Lips:

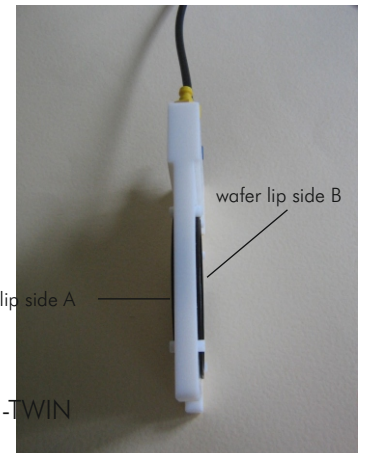
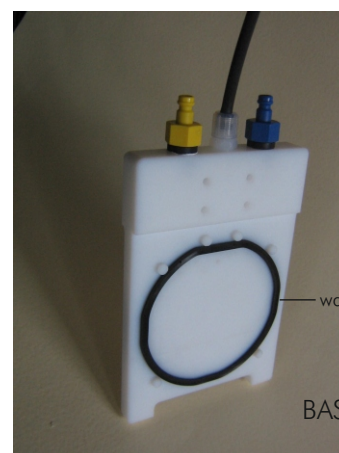
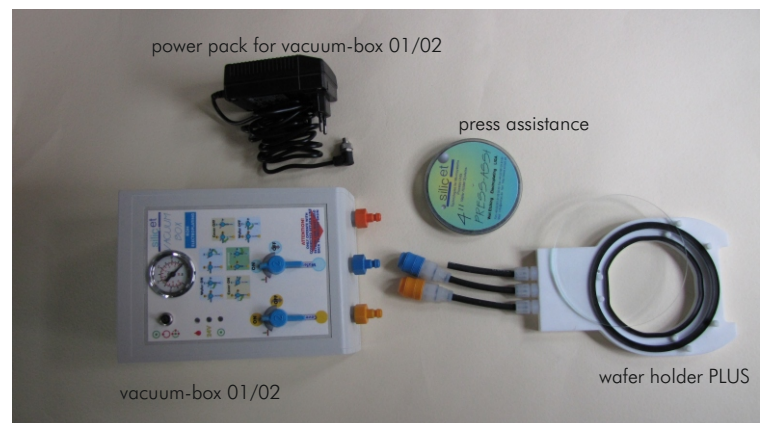
Supply line:

Rack:

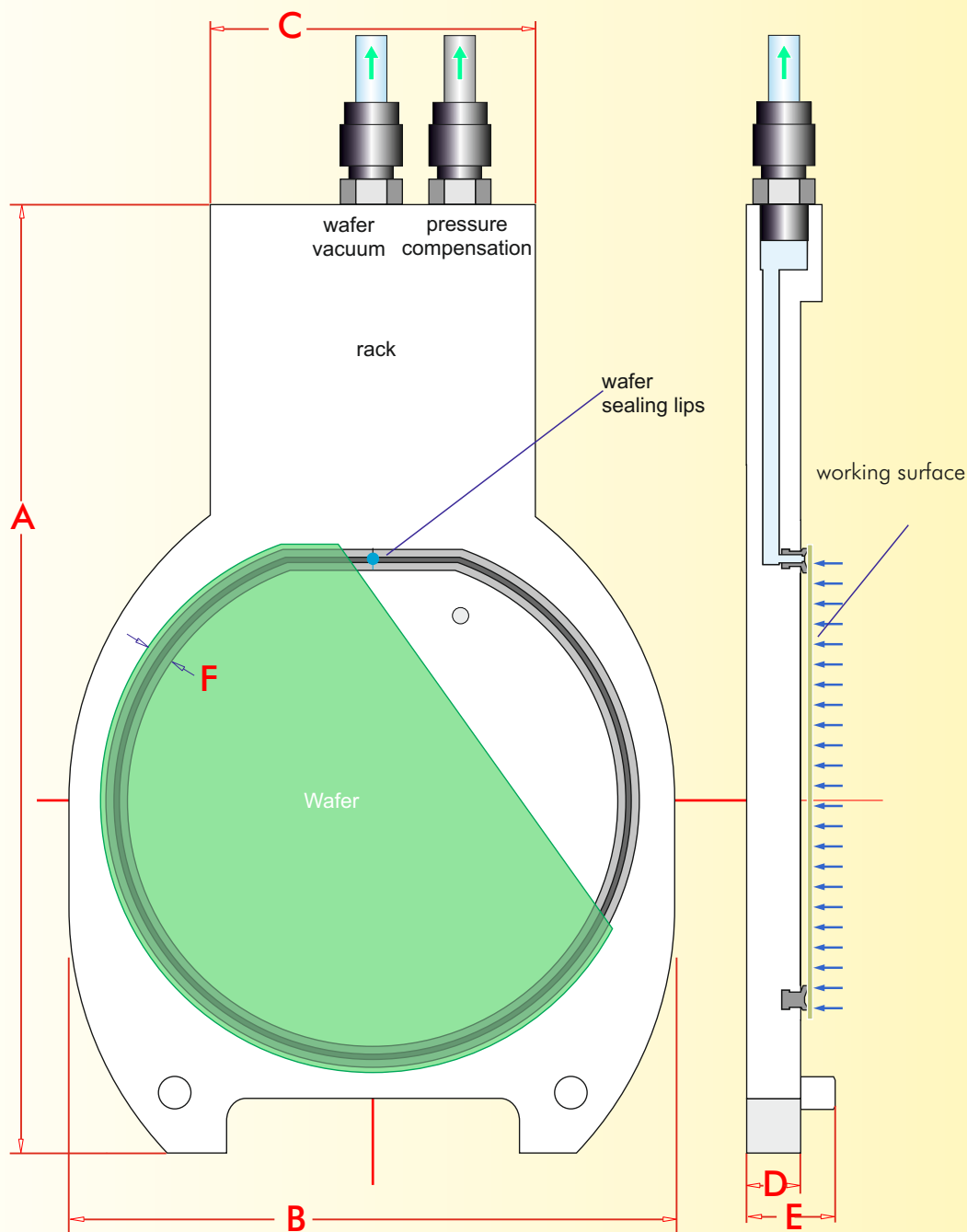
EPDM/FPM peroxide cured and sulfure-free

2 Norprene or Viton-connecting tubes

PTFE



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VACUUM-HOLDER BASIC



Dimension	2"	3"	4"	5"	6"	8"
A - length	105 mm	135 mm	185 mm	200 mm	227 mm	260 mm
B - total width	65 mm	87 mm	132 mm	145 mm	160 mm	212 mm
C - width neck	65 mm	50 mm	80 mm	80 mm	80 mm	80 mm
D - thickness	12 mm	12 mm	12 mm	14 mm	14 mm	14 mm
E - compl. thickness	16 mm	16 mm	16 mm	18 mm	18 mm	18 mm
F - edge exclusion	5 mm	5 mm	5 mm	5 mm	5 mm	5 mm